

Opportunity Title: Developing Electroplating Processes by Controlling Crystal Nucleation and Growth

Opportunity Reference Code: DOE-MSIPP-18-8-ANL

Organization U.S. Department of Energy (DOE)

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How to Apply A complete application must include the following to be considered:

- Completion of all required fields in the application and successful application submission
- Undergraduate or graduate transcripts as appropriate
- Two recommendations

If you have questions, send an email to Kerri Fomby at kerri.fomby@orau.org. Please include the reference code for this opportunity in your email.

For Technical information, contact Lisa Reed at lisareed@anl.gov.

Application Deadline 1/12/2018 11:59:00 PM Eastern Time Zone

Description The Minority Serving Institutions Partnership Program (MSIPP) Internships is a new program to promote the education and development of the next generation workforce in critical science, engineering, technology, and math (STEM) related disciplines that complement current and future missions of DOE national laboratories. The MSIPP Internship program is designed to provide an enhanced training environment for next generation scientists and engineers by exposing them to research challenges unique to our industry.

MSIPP Interns will be given the opportunity to complete Summer Internships aligned with ongoing U.S. Department of Energy Office of Environmental Management (DOE-EM) research under the direction of a host national laboratory. The internship will be performed at the host national laboratory, utilizing their facilities and equipment under the guidance of a research staff member.

Minority Serving Institutions are institutions of higher education enrolling populations with significant percentages of undergraduate minority students.

Project: This project explores the many applications of electroplating, from x-ray masks to magnetic nanowires or transition edge sensors. The deposited materials are ranging from tens of nanometers to microns in size. Crystal morphology determines the physical properties of the deposit. Pulse current deposition will allow to obtain a finer grained deposit with better properties than direct current plated coatings. Hardness of the deposit largely depends upon the grain size. By favoring grain nucleation over grain growth harder deposits can be obtained. Proper use of pulse plating can produce deposits with tailor-




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made properties. A few studies on influence of the pulse plating on stress in thin films of metals (Bi, Au, Cu) or magnetic materials are available in the literature. The relation between the process parameters, deposit nanostructure, thickness uniformity, effects of surfactants or additives and resulting residual stress has not yet been much discussed for the fabrication of thick ($> 100\ \mu\text{m}$) layers by using pulse plating.

Location: This internship will be located at Argonne National Laboratory.

Salary: Selected candidate will be compensated by either a stipend or salary, and may include one round trip domestic travel to and from the host laboratory. Stipends and salaries will be commensurate with cost of living at the location of the host laboratory. Housing information will be provided to interns prior to arrival at the host laboratory, and will vary from lab to lab.

Application Deadline: January 12, 2018

Expected Start Date: The program is 10 weeks in duration, starting May 21, 2018. Start date is flexible based on laboratory and candidate availability.

Qualifications Eligible applicants must:

- Be a citizen of the United States,
- Be at least 18 years of age,
- Currently enrolled as a full-time undergraduate or graduate student at an accredited Minority Serving Institution, <http://orise.ornl.gov/msipp/documents/approved-msi-school-list.pdf>,
- Working toward a science, technology, engineering, or mathematics (STEM) degree,
- Have an undergraduate or graduate cumulative minimum Grade Point Average (GPA) of 3.0 on a 4.0 scale, and
- Pass a drug test upon selection to participate in the MSIPP

*The process and timing for drug testing varies from lab to lab. Use of Marijuana/Cannabis or its derivatives if prescribed is legal in some states. However, having these drugs in your system is NOT legal at United States Federal Contractor sites and National Laboratories.

Required Knowledge, Skills, Work Experience, and Education

Successful candidates will:

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- Be a current undergraduate or graduate student pursuing a degree in chemistry, physics, materials sciences, or related field.

Desired Knowledge, Skills, Work Experience, and Education

It is desirable for the candidate to have:

- Chemistry lab work experience.

Eligibility Requirements

- **Citizenship:** U.S. Citizen Only
- **Degree:** Currently pursuing a Bachelor's Degree or Master's Degree.
- **Overall GPA:** 3.00
- **Discipline(s):**
 - **Chemistry and Materials Sciences** (12 👁)
 - **Physics** (16 👁)

Affirmation

I certify that I am at least 18 years of age and a US citizen, and am currently enrolled as a student in a degree seeking undergraduate or graduate program in a STEM field at an accredited Minority Serving Institution (MSI).